

IN THE ABSTRACT:

Please cancel the current abstract and insert the following.

An exposure apparatus includes a plurality of purge spaces delimited along the optical path between the laser light source and the substrate by housings the boundary members of which are invisible to the exposing light, and pressure regulating unit for exercising control in such a manner that the pressure within each purge space attains a predetermined value. In the exposure apparatus that is purged in sections, therefore, it is possible to reduce the amount of deformation of the end faces between mutually adjacent purge spaces, e.g., the end face of a projection optics unit.

-- An exposure apparatus for performing exposure of patterns of a reticle onto a substrate
includes a first housing covering an optics space containing members of an optical system of an
optical path of exposing light, a second housing covering a drive space containing driving
members, which adjoins the optics space, members transparent to exposing light provided at
boundaries of the adjacent first and second housings, a gas supplier which supplies the interior of
the first and second housings with a purging gas, pressure sensors which sense pressures inside
respective ones of the first and second housings, and a control unit which controls the gas
supplier on the basis of outputs from the pressure sensors in such a manner that pressures within
the respective first and second housings will attain respective ones of predetermined pressures.--